

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	873	(wafer substrate) same (inert adj gas argon) same rough\$4	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM- TDB	2003/10/0 7 15:59	
2	BRS	L2	242	(wafer substrate) same (inert adj gas argon) same rough\$4 and (Cr chromium)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM- TDB	2003/10/0 7 16:03	